

Photomask Cleaner - Ultratech 603 Mask/Substrates cleaner

- Uses non-abrasive high-pressure jets to effectively clean particulates from photomasks & wafers.
- Water pressure adjustable up to 2,500 psi with high pressure pump.
- Can accommodate different substrates such as:
 - Masks (4" to 6")
 - Wafers (4" to 6")
 - clean time (up to 3 min)
- Spindle speeds up to 3,000 rpm
- Filtration up to 2-micron

